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Advances in X-Ray/EUV Optics and Components XIII

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Introduction

This volume contains papers presented at the conference on Advances in X-Ray/EUV Optics and Components XIII, held 20 August 2018 in San Diego, California, USA, as part of the SPIE Optics + Photonics symposium.

The conference was composed of four oral sessions covering the fields Metrology, Multilayers, Gratings and Mirrors, and Sources and Crystal Optics. It was complemented by a poster session.

This conference was focused on technological developments in x-ray/EUV optics for synchrotron and FEL beamlines, laboratory sources, laser and plasma physics, medical imaging, and astronomy. Accordingly, the applications covered a wide spectral range from vacuum ultraviolet to hard x-rays. Topics related to adaptive x-ray optics were largely presented at another conference at the same symposium.

Scheduled for one day of oral presentations accompanied by an evening poster session, the conference was well attended. We would like to thank the authors, speakers, session chairs, program committee members, and the conference participants for their contributions, and the SPIE staff for their help in making it a success.

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